



partnering for process control

You are cordially invited to attend the following talks involving Nova technology and customer collaboration:

SPIE. ADVANCED LITHOGRAPHY

CONFERENCE 10145 **Metrology, Inspection, and Process Control for Microlithography XXXI**

- February
27
Monday
- Electrical test prediction using hybrid metrology and machine learning [10145-3]**
Speaker: Mary Breton, IBM Corp. (USA)
1:40 PM SESSION 2 (Hybrid Metrology)
- February
27
Monday
- Hybrid scatterometry measurement for BEOL process control [10145-5]**
Speaker: Pdraig R. Timoney, GLOBALFOUNDRIES (USA)
2:20 PM SESSION 2 (Hybrid Metrology)
- March
1
Wednesday
- Complex metrology on 3D structures using multi-channel OCD [10145-48]**
Speaker: Taher Kagalwala, GLOBALFOUNDRIES (USA)
4:00 PM SESSION 11 (Optical Metrology)
- March
1
Wednesday
- Scatterometry control for multiple electron-beam lithography [10145-51]**
Speaker: Yoann Blancquaert, CEA-LETI (France)
5:00 PM SESSION 11 (Optical Metrology)
- March
1
Wednesday
- Advanced optical modeling of TiN metal hard mask for scatterometric critical dimension metrology [10145-52]**
Speaker: Carsten Hartig, GLOBALFOUNDRIES Dresden Module One LLC & Co. KG (Germany)
5:20 PM SESSION 11 (Optical Metrology)
- March
2
Thursday
- Materials characterization for process integration of multi-channel gate all around (GAA) devices [10145-66]**
Speaker: Raja Muthinti, IBM Corp. (USA)
3:30 PM SESSION 15 (Late Breaking News)
- March
2
Thursday
- Application of advanced hybrid metrology method to nanoimprint lithography [10145-108]**
Speaker: Ilya Osherov, Nova Measuring Instruments Ltd. (Israel)
4:50 PM SESSION 15 (Late Breaking News)

SHORT COURSE

- February
26
Sunday
- Scatterometry in Profile, Overlay and Focus Process Control [SC1100]**
Instructors: Hugo Cramer, ASML Netherlands B.V. (Netherlands);
Igor Turovets, Nova Measuring Instruments Ltd. (Israel)
1:30 PM - 5:30 PM

For more information visit the official SPIE Advanced Lithography website:
<http://spie.org/conferences-and-exhibitions/advanced-lithography/conferences>